

Title (en)

CLEANING COMPOSITION, METHOD FOR CLEANING A SILK SCREEN AND CLEANING DEVICE

Title (de)

REINIGUNGSMITTEL, VERFAHREN ZUR REINIGUNG VON SIEBDRUCKSCHABLONEN UND VORRICHTUNG ZUR REINIGUNG

Title (fr)

COMPOSITION NETTOYANTE, PROCEDE POUR NETTOYER UN ECRAN DE SERIGRAPHIE ET DISPOSITIF DE NETTOYAGE

Publication

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Application

EP 00969652 A 20001019

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Abstract (en)

[origin: WO0129168A1] The invention concerns a cleaning composition comprising an aqueous solution containing between 0.05 to 5 wt. % of sodium metaperiodate and between 0.05 and 0.75 wt. % of sulphuric acid, and an aqueous solution of 0.5 to 90 wt. % of a mixture of dialkylesters and of 0.5 to 50 wt. % of a non-ionic surfactant. The method for cleaning a silk screen consists in exposing it to such a composition to eliminate ink, the masking product and the ghost image. The device for cleaning comprises a first section (4) wherein are a first ramp (26) of nozzles for spraying a cleaning composition on the screen (2) and a second ramp (32) of nozzles for spraying water under high pressure, and with which is associated a drain tank (20) for recovering the cleaning product and a reservoir (14) of cleaning product separate from the drain tank (20).

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Cited by

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